

CLAIM AMENDMENTS

1 - 14. (canceled)

1 15. (currently amended) A MOCVD apparatus for gas phase
2 deposition [[with]] comprising:

3 a chamber;
4 a partition subdividing the chamber into at least two
5 compartments;

6 respective gas inlets {4, 5}, characterized by opening
7 into the compartments and connectable to respective gas supplies;
8 and

9 means for flexibly switching the inlets and thus flexibly
10 introducing gases into the apparatus.

1 16. (currently amended) The MOCVD apparatus according
2 to claim 15 characterized in that, further comprising
3 between the gas inlets {4, 5} and the supply vessels
4 supplies for the gases to be fed into the apparatus, gas collecting
5 lines {51, 52, 53} are provided in which there are arranged at
6 least two three-way valves {V1, V2, V3} shiftable between a first
7 position feeding one of the gases to one of the compartments and
8 the other of the gases to the other of the compartments and a
9 second position feeding the other gas to the one compartment and
10 the one gas to the other compartment.

17. (canceled)

1 18. (new) The MOCVD apparatus according to claim 15,
2 further comprising
3 quick-connect couplings between the inlets and the
4 supplies.